

## Supporting Information

### Synergistic Enhancement by MoS<sub>x</sub> and Sulphate on Amorphous Polymetallic Oxides Nanosheets for Oxygen Evolution Reaction

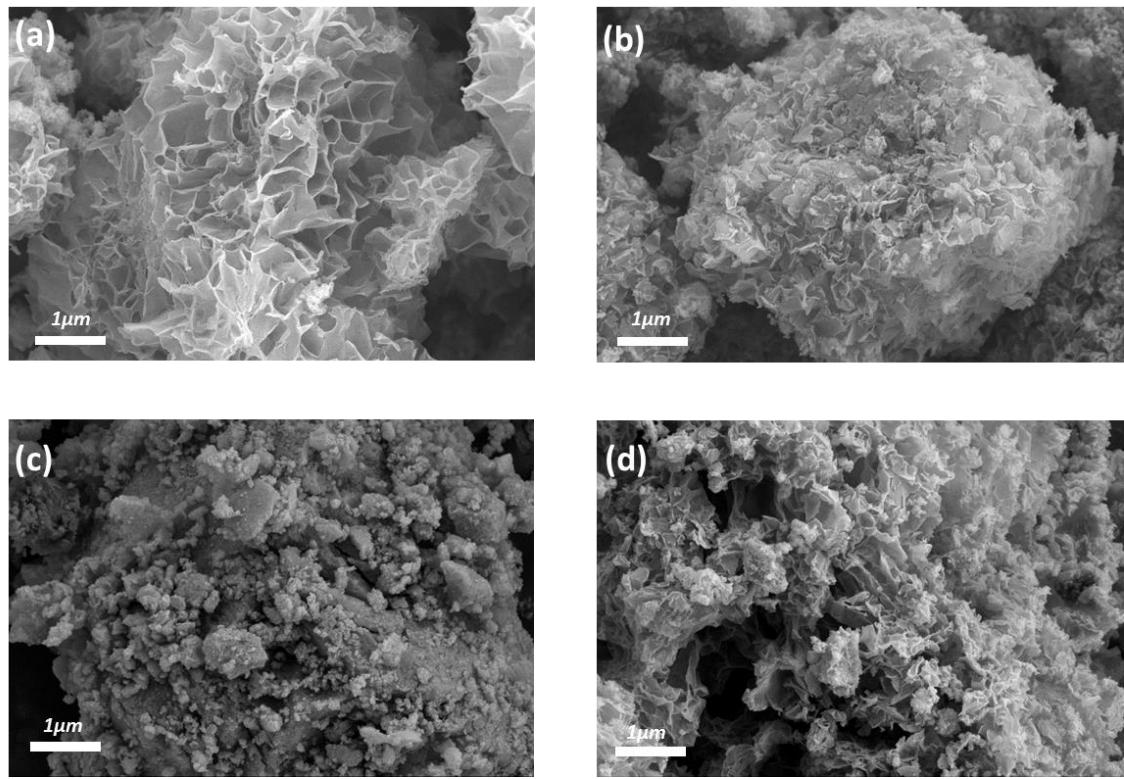
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Wu, Yihua Cao, Xin Zhang

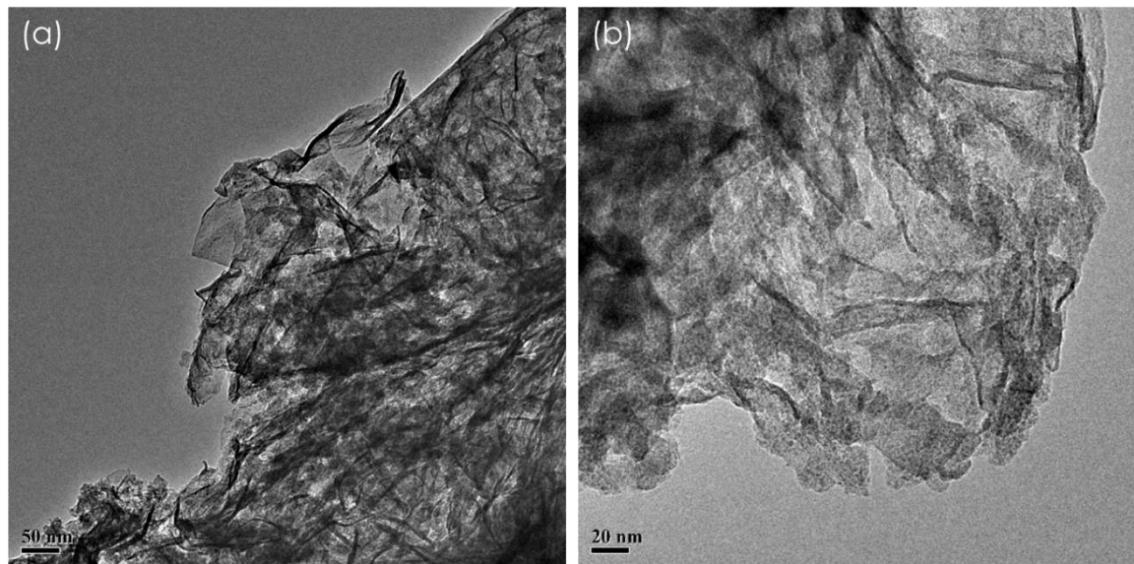
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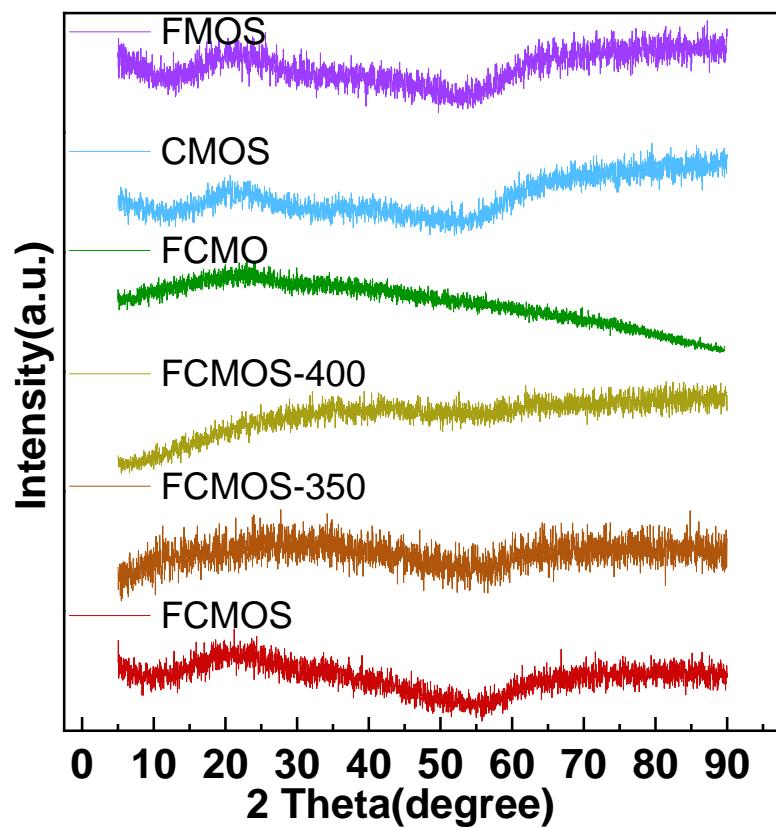
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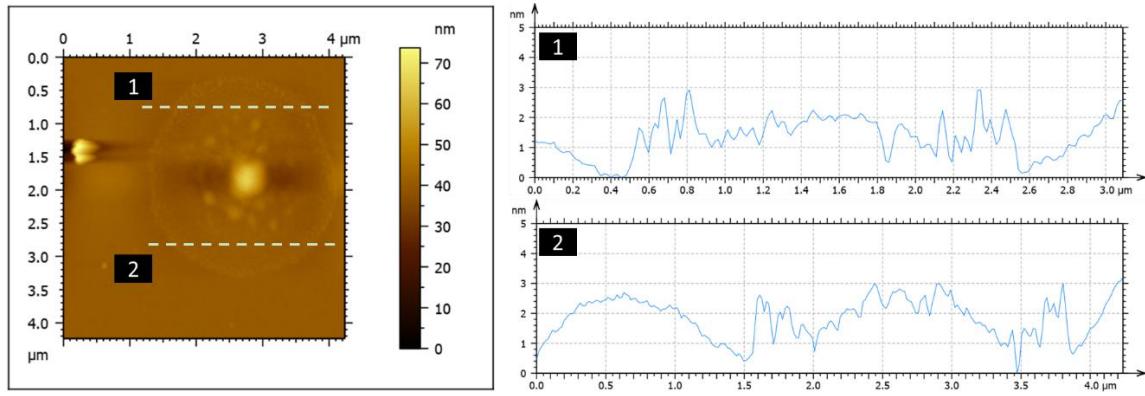
**Figure S1.** SEM images of (a) FCMOS, (b) CMOS, (c) FMOS and (d) FCMO



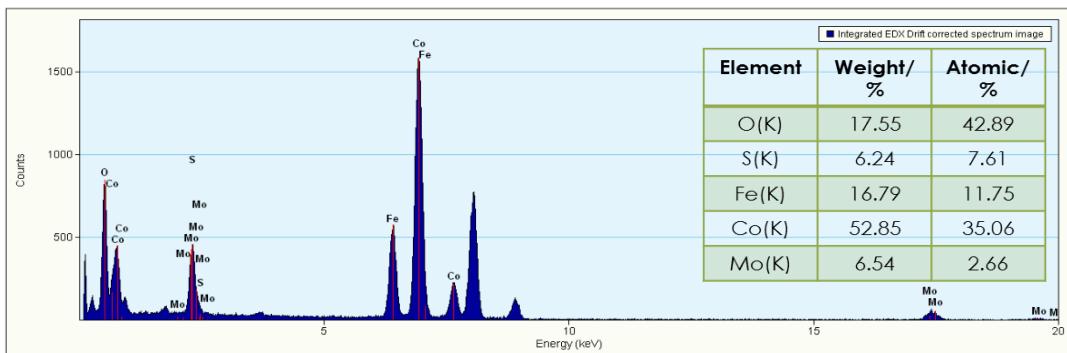
**Figure S2** HRTEM images of FCMOS



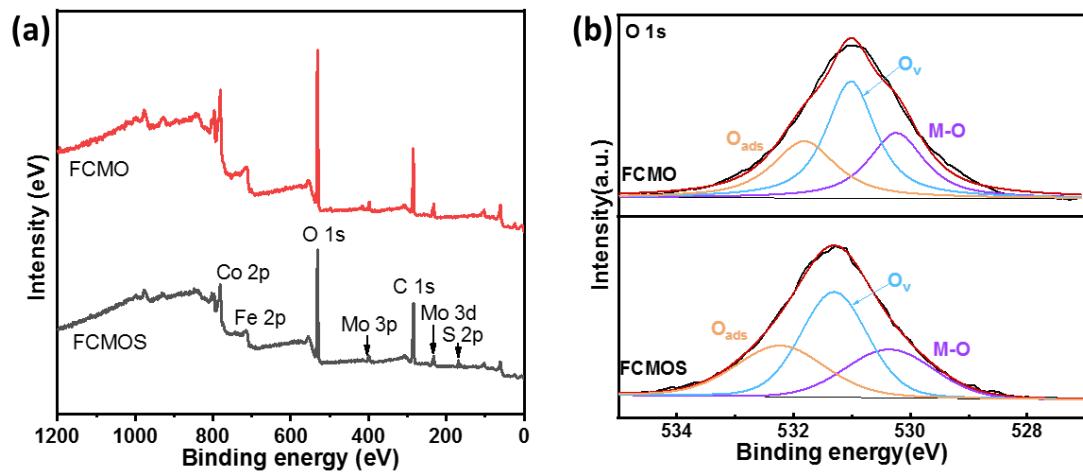
**Figure S3.** XRD spectra of FCMOS, FCMOS-350, FCMOS-400, FCMO, CMOS and FMOS.



**Figure S4.** AFM of the FCMOS



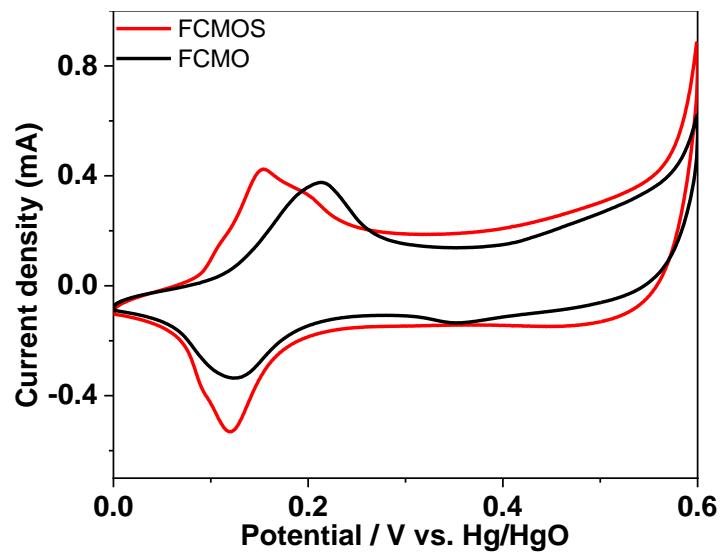
**Figure S5.** EDS spectrum of as-synthesized FCMOS



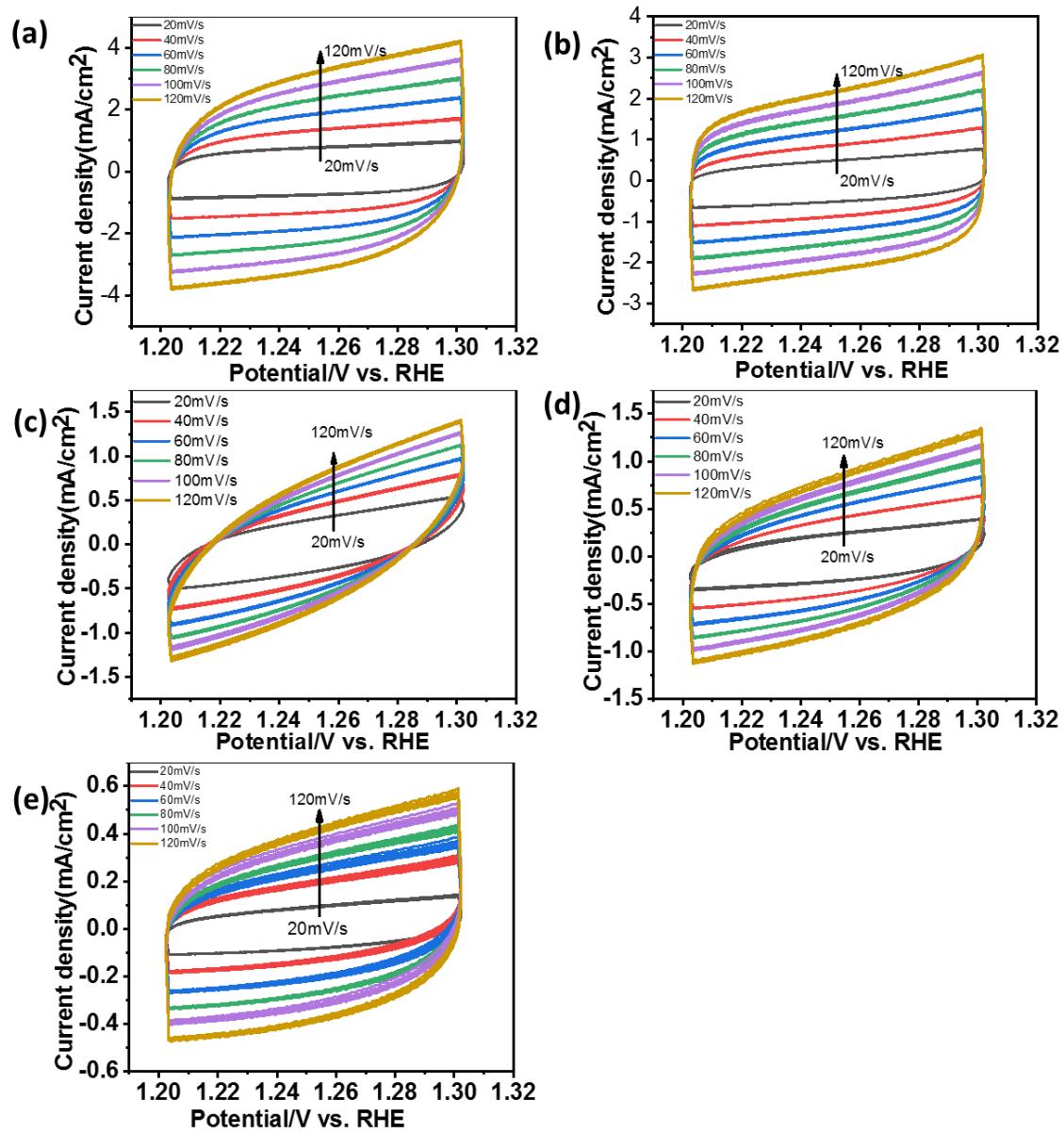
**Figure S6.** (a)The survey spectra of FCMOS and FCMO; (b) XPS spectra of O 1s of FCMOS and FCMO

**Table S1.** Comparison of the OER performance of various catalysts in 1.0 M KOH solution

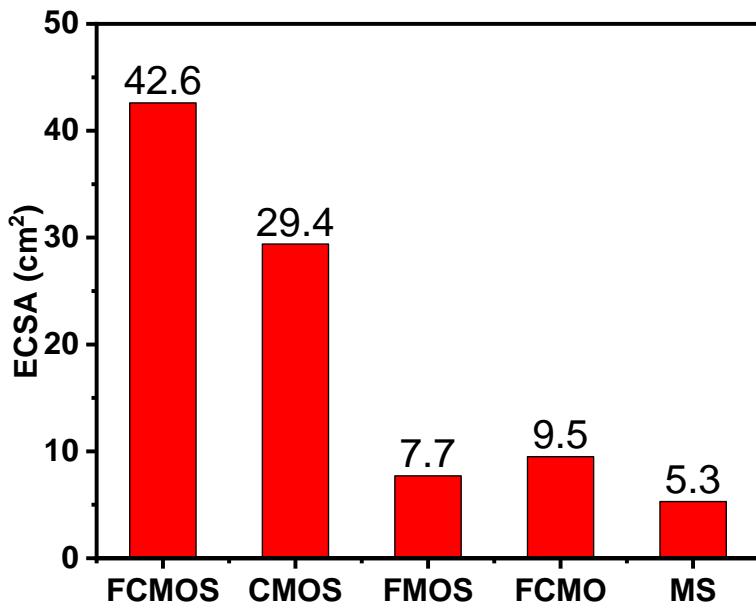
catalysts	Overpotential at current density (mV)		Tafel (mV dec <sup>-1</sup> )	Ref.
	10 mA cm <sup>-2</sup>	100 mA cm <sup>-2</sup>		
<b>FCMOS</b>	<b>260</b>	<b>320</b>	<b>47</b>	<b>This work</b>
<b>FCMO</b>	<b>290</b>	<b>420</b>	<b>93</b>	<b>This work</b>
Vo-(Co,Fe) <sub>3</sub> O <sub>4</sub> /CC	286	-	41	1
holey NiCoS-NS	280	-	85	2
S-NiFe <sub>2</sub> O <sub>4</sub> /NF	420	-	118.1	3
Co,Fe-MoS <sub>2</sub>	260	370	117	4
FeCoMo	277	336	27.74	5
CoMoS <sub>3</sub>	320	-	-	6
CoFeS	290	-	52.6	7
SnCoFe-Ar	300	-	42.3	8
A-CoS <sub>4.6</sub> O <sub>0.6</sub> ONCs	290	-	67	9
CMO	340	-	49	10
M-Co <sub>3</sub> O <sub>4</sub> /NPC	302	-	84	11



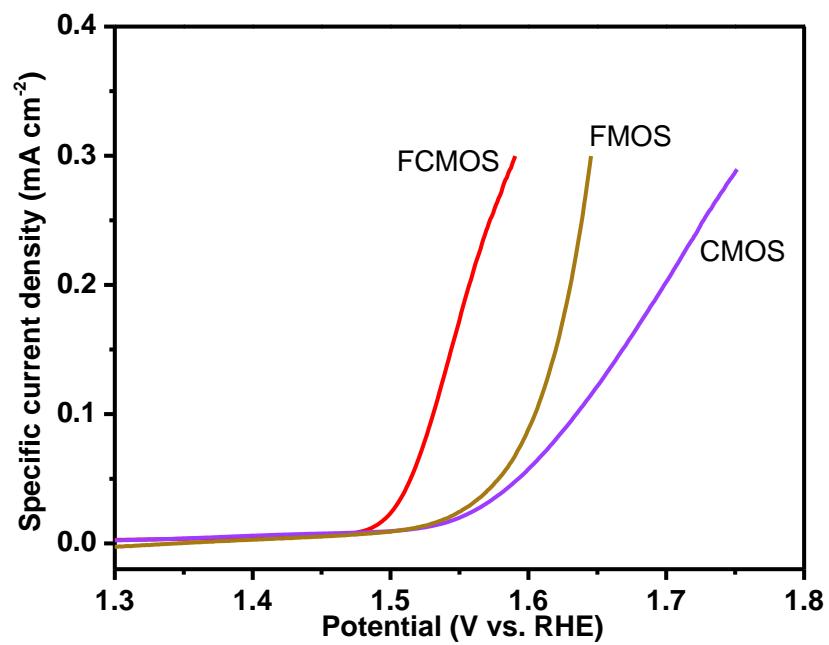
**Figure S7.** Cyclic voltammograms of FCMOS and FCMO



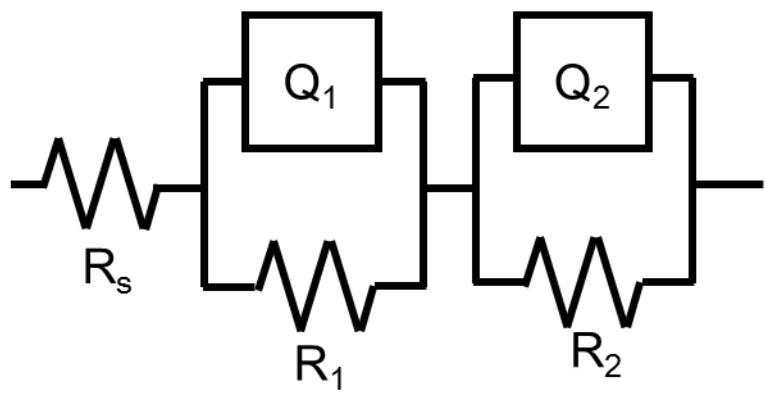
**Figure S8.** Cyclic voltammograms of (a) FCMOS, (b) CMOS, (c) FMOS, (d) FCMO, and (e) MS at scan rates from 20 to 120 mV/s.



**Figure S9.** ECSA of FCMOS, CMOS, FMOS, FCMO and MS



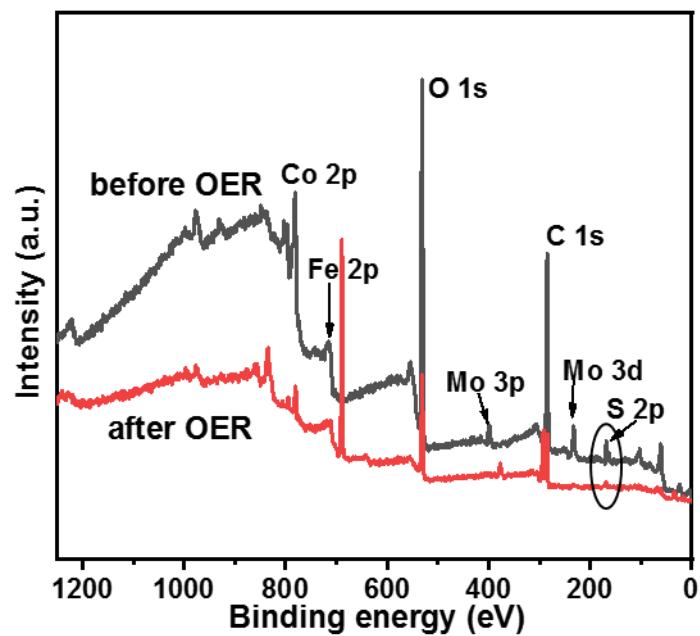
**Figure S10.** ECSA-normalized LSV curves



**Figure S11.** Electrical equivalent circuit model used for fitting of EIS

**Table S2.** Estimates of the equivalent circuit parameters for different samples

Samples	$R_s(\Omega \cdot \text{cm}^2)$	$10^2 Q_1(\text{S} \cdot \text{cm}^{-2} \cdot \text{s}^n)$	$n_1$	$R_1(\Omega \cdot \text{cm}^2)$	$10^2 Q_2(\text{S} \cdot \text{cm}^{-2} \cdot \text{s}^n)$	$n_2$	$R_2(\Omega \cdot \text{cm}^2)$
FCMOS	0.948	5.093	0.906	1.192	29.660	0.562	0.473
FCMO	1.094	1.420	0.872	6.825	2.808	0.628	0.802
CMOS	0.085	4.269	0.882	40.400	1.262	0.302	1.491
FMOS	0.544	0.761	0.949	29.200	0.989	0.741	26.340
MS	0.552	0.271	0.937	30.340	27.760	0.832	0.177



**Figure S12.** Comparison of survey XPS spectra between before and after OER stability testing of the FCMOS in 1 M KOH

## Reference

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